

AMENDMENT

In response to the Advisory Action of May 12, 2003 please amend the above-identified application as follows:

In the Claims:

Please amend claim1 as follows:

1. (THRICE AMENDED) A polishing-dressing head for a polishing apparatus comprising:

a plurality of substrate head assemblies each having a lower nesting surface opposed to an upper surface of a polishing pad, said lower nesting surface releasably holds a substrate to be polished, said substrate head assemblies, each rotating along a central axis thereof and polishing the substrates on an outer radial portion of said rotating polishing pad;

annular dressing rings for dressing said polishing pad, said dressing rings are positioned coaxially encircling each nested substrate, said annular dressing rings are ~~removably attached~~ to said lower surface of said substrate head assemblies.
